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### Prof. Dr. Johann W. Bartha

Inst. f. Halbleiter und Mikrosystemtechnik Technische Universität Dresden

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VT L01 a 13:59



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## About the instructor



CV: Johann W. Bartha

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Prof. Dr. Johann W. Bartha received a Diploma and PhD. degree in solid state physics at the University of Hannover, Germany. He was two years Post Doc at the IBM T. J. Watson Research Center Yorktown Heights, N. Y. were he investigated Metal Polyimide interfaces for applications in multi layer ceramic packaging. 1985 he joined the IBM German Manufacturing Technology Center (GMTC) at Sindelfingen Germany as staff member and became responsible for plasma based technologies in semiconductor processing as a senior staff member. 1994 he accepted a professorship at the University of Applied Sciences at Münster, Germany where he established a laboratory for micro manufacturing. 1999 he accepted a C4 professorship as head of the chair for Semiconductor Technology at the Dresden University (TUD). From March 2003 to April 2019 he was director of the Institute of Semiconductor- and Microsystems technologies at TUD and established a strong collaboration between Dresden University and the local semiconductor Industry. The research focus at his department was BEOL processing (PVD, ECD, CMP) including barrier characterization. He established in situ monitoring techniques for atomic layer deposition in the cleanroom lab. Since 4/2019 he is retired but continues acting as senior professor at IHM.

Prof. Bartha is member of the DPG (German physical society), and foundation member of the Silicon Saxony association. He was co-organizer of several international conferences in the field of microelectronics (IITC - International Interconnect Conference, European AEC/APC, ICPT 2007 - Int. Conf. on Planarization Technology, IWFIPT 2007, MRS Spring Symposium on CMP 2004 and 2010) and co-founder of the Dresden Summer School Microelectronics. He was non voting member in the board of the FhG-CNT until 2009 (a joint R&D organization of AMD, Qimonda and Fraunhofer) and was head of the NaMLab gGmbH scientific board (materials research company owned by TUD) until 2018.

#### L01



- Literature:

I will distribute later a booklet (pdf) containing much of the content. I am not aware of a book, that matches with the lecture as assembled here.

- Examination:

If the number of students to be examined exceeds 20 (currently the case!), the exam will be held as written test.

- Consultation:

I will invite within the next few weeks to a consultation as ZOOM conference. In urgent cases do not hesitate to contact me via e-mail!

L01

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## O. Introduction

- Vacuum techn. & relation to semiconductor manufacturing
- some history
- back to manufacturing





### IC - Production: Workplaces - IFD P200



#### L01



### Man & Production: Workplaces - IFD P200



#### L01



### "OPEN" - Cleanroom - IFD P200 - Production Bay



#### L01





#### L01





#### L01





#### L01





#### L01



### Cleanroom - Clean Subfab Area - Basement



#### L01



Bulk-Gas		Consumption m <sup>3</sup> / h
Nitrogen	N <sub>2</sub>	10 000
Oxygen	<b>O</b> <sub>2</sub>	300
Argon	Ar	60
Hydrogen	H <sub>2</sub>	30
Helium	Не	20





#### L01



### Wafer-Fab – Facilities – Special Gases



200	
320	130
50	50
80	30
650	270
680	20
1300	800
	320 50 80 650 680 1300

~200km

Jultraclean, specially welded piping







### Back to the beginning of vacuum technology

VTL01 c 22:04



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### Vacuum Technology Today in microelectronics

VTL01d 09:04



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L01



Chapters

- **O.** Introduction
- 1. Gas kinetic
- 2. Pressure Ranges
- 3. Vacuum technical terms
- 4. Vacuum generation
- 5. Pressure measurement

#### L01







- 0. Introduction
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#### L01





#### L01





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L01









VTL01e 23:39

### **O.** Introduction

Air pressure as a force to the walls of an empty container -> Pressure = Force/Area

## 1. Gas kinetic

- 2. Pressure Ranges
- 3. Vacuum technical terms
- 4. Vacuum generation
- 5. Pressure measurement

#### L01





### Blackboard: What is pressure?





#### L01



# Blackboard: What is pressure?

What is Pressurez Unit -> Pa (=N/m2) Pressure = Force / Area =(mass · accelleration) Area = mass · (Velocity change per time unit) / Area = (mass · limes velocity change) / (time unit - Area) - change in momentum /(time unit. Area) P=FIDA = m-a/DA = (m. AV/At)/DA= DP/DA-At Pressure is the "transfor" of momentum to a wall per time-and area unit



## What is Pressure? Unit is Pa (=N/m²)

 $\mathbf{v}$ 

#### L01



```
What is Pressure?
Unit is Pa (=N/m<sup>2</sup>)
Pressure = Force / Area
```

#### L01



```
What is Pressure?
Unit is Pa (=N/m<sup>2</sup>)
Pressure = Force / Area
= mass · accelleration / Area
```





```
What is Pressure?
Unit is Pa (=N/m<sup>2</sup>)
Pressure = Force / Area
= mass · accelleration / Area
```

= mass  $\cdot$  (velocity change per time unit) / Area

L01





= (mass  $\cdot$  times velocity change) / time unit  $\cdot$  Area











#### L01









 $P = F / \Delta A = m \cdot a / \Delta A = (m \cdot \Delta v / \Delta t) / \Delta A = \Delta p / \Delta A \cdot \Delta t$ 

Pressure is

the "transfer" of momentum to a wall per time- and area unit



## Blackboard:

## New way of understanding the gas properties:

New way of understanding the gas properties:

approximations

- Gas particles are spheres
- no forces except when collide
- movement independent from each other
- isotropy (no special direction)
- law of conservation , energy & momentum

- velo ity of individual particles charges frequently due to collisions

LC\_



New way of understanding the gas properties:

Model approximations

- Gas particles are spheres of atomic dimension
- no forces except when collide
- movement independent from each other
- isotropy (no special direction)
- law of conservation of energy and momentum holds
- velocity of individual particles changes frequently due to collisions

#### L01





## »Wissen schafft Brücken.«

